Session Program

1–2 Jul 2013

Training on semiconductor devices, design and manufacturing

Semiconductor Manufacturing Processes

Katane Palace Hotel, Catania (Italy)
Via Finocchiaro Aprile, 110 - Catania (Italy)

Monday 1 July

09:00

Semiconductor Manufacturing Processes

Session | **Location:** Katane Palace Hotel, Catania (Italy), Via Finocchiaro Aprile, 110 - Catania (Italy) | **Convener:** Dr Giuseppe Arena

09:00–09:30

Brief Introduction of STMicroelectronics and Microelectronics Historical Notes

Speaker
Dr Giuseppe Arena

Location
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09:30–10:40

Semiconductors Processing and Devices Fabrication - 1st part (crystal growth and epitaxy, thermal oxidation, ion implantation and diffusion)

Speaker
Dr Giuseppe Arena

Location
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10:40–11:00 **Coffee break**

11:00–12:30

Semiconductors Processing and Devices Fabrication – 2nd part (Thin film deposition, photolithography, plasma basics, etching and new trends in microelectronics industry)

Speaker
Dr Giuseppe Arena

Location
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12:45–14:00 **Lunch break**

14:00